

- Based on Proven and Reliable SR Series Design
- Tailored for Research Environments, Incorporating Established SR4000HT Capabilities in a Smaller Package

Wide Process Window MOCVD for Power and Optoelectronic Devices

Advantages

- High Growth Rates
- Carbon Background Concentration Control and Flexibility
- High InGaN Growth Temperature
- High Al Content AlGaN

Applications

HEMT, PN Diodes, Lasers, RGB to UV LED





SR4000HT-RR Specifications

Reactor type	Face up, horizontal with rotation
Wafer size	2" x 3 or 4" x 1
Heating system	Two zone, up to 1350 °C
Growth pressure	10 kPa up to 100 kPa
Size	One cabinet only for manifold, reactor and exhaust
Sources	Eight (8) metalorganic Two (2) hydride lines

About Us

Taiyo Nippon Sanso Corporation (TNSC) was the first company to develop and introduce its own commercial metal organic chemical vapor deposition (MOCVD) systems in 1983. TNSC equipment has received praise for its world-class performance and stability. TNSC is also uniquely qualified to provide total solutions for MOCVD applications, including MOCVD equipment, purification and abatement solutions, specialty gases, and gas handling equipment.

Also TNSC is an industrial gas manufacturer with abundant experience and unique technological capabilities supporting a wide range of industries, including the electronics, steel, chemical, automobile, construction, shipbuilding, food/beverage, and medical care sectors. TNSC is expanding globally with products developed in-house, and products and technologies acquired through open innovation platforms.



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